

**AMENDMENTS TO THE SPECIFICATION**

**IN THE SPECIFICATION:**

On page 6, amend the paragraph in lines 18-19 as follows:

Finally, after the door of the adhesion chamber 2 is opened, **and** the substrate 1 is taken out.

**CLAIM SET AS AMENDED**

Please cancel claim 15 without prejudice or disclaimer to the subject matter contained therein.

Please amend the claims as follows:

1. (Previously Amended) A method of preventing generation of particles in a chamber, the method comprising:

mounting a substrate within a chamber of a gas-exposure equipment;

decreasing a pressure within the chamber;

injecting a surface treatment gas into the chamber, the surface treatment gas converting a surface of the substrate into an organic material;

increasing the pressure within the chamber to greater than or equal to atmospheric pressure by injecting a nitrogen gas into the chamber; and

drawing out the surface treatment gas from the chamber while injecting the nitrogen gas into the chamber and preventing atmospheric air and moisture from penetrating the chamber.

2-3. (Canceled)

4. (Currently Amended) The method as claimed in claim 1, wherein the surface treatment gas includes HMDS gas.

5. (Canceled)

6. (Original) The method as claimed in claim 1, wherein the chamber includes evacuation lines and ejection lines.

7. (Previously Amended) The method as claimed in claim 6, wherein the injecting nitrogen gas into the chamber includes injecting the nitrogen gas through the ejection lines.

8. (Currently Amended) The method as claimed in claim 6, wherein the step of evacuating includes evacuating the surface treatment gas through the evacuation lines.

9. (Original) The method as claimed in claim 1, wherein the substrate is a thin film transistor substrate.

10. (Original) The method as claimed in claim 9, wherein the thin film transistor substrate includes at least one of a gate electrode, a source electrode, a drain electrode, and a pixel electrode.

11. (Currently Amended) The method as claimed in claim 1, wherein the substrate includes a color filter substrate.

12. (Original) The method as claimed in claim 11, wherein the color filter substrate includes at least one of a color filter and a black matrix.

13. (Currently Amended) A method to prevent generation of contaminating particles in a chamber, the method comprising:

evacuating an ordinary gas within said chamber;

injecting a treatment gas into said chamber to convert ~~treat~~ a surface of a substrate into an organic material;

increasing a pressure in said chamber to greater than or equal to atmospheric pressure by injecting a moisture displacing gas into the chamber; and

withdrawing said treatment gas from said chamber while injecting the moisture displacing gas into said chamber and preventing atmospheric air from entering the chamber.

14. (Original) The method of claim 13, wherein said moisture displacing gas is nitrogen.

15. (Canceled)

16. (Canceled)

Please add the following claim:

17. (New) A method to prevent generation of contaminating particles in a chamber, the method comprising:

evacuating an ordinary gas within said chamber;

injecting a treatment gas into said chamber to treat a surface of a substrate;

increasing a pressure in said chamber to greater than or equal to atmospheric pressure by injecting a moisture displacing gas into the chamber; and

withdrawing said treatment gas from said chamber while injecting the moisture displacing gas into said chamber and preventing atmospheric air from entering the chamber, wherein said treatment gas is HMDS.

**REMARKS**

Applicant thanks the Examiner for the very thorough consideration given the present application.

Claims 1, 4, 6-14 and 17 are now pending in this application. Claims 1, 13 and 17 are independent. Claim 15 has been canceled. Claim 17 has been added. Claims 4, 8, 11 and 13 have been amended.

Reconsideration of this application, as amended, is respectfully requested.

**Specification Amendments**

The specification has been amended to correct a grammatical informality on page 6.

**Rejection Under 35 U.S.C. § 102**

Claims 13 and 14 stand rejected under 35 U.S.C. § 102(e) as being clearly anticipated by Shimizu et al. This rejection is respectfully traversed.

Applicants thank the Examiner for the indication of allowable subject matter in paragraph 5 of the final rejection. It is respectfully asserted that the allowable subject matter has been incorporated into independent claim 13. Specifically, claim 13 now recites each of the method steps specifically pointed out by the Examiner, with the exception of noting that the moisture displacing gas is nitrogen. In any event, based upon the Examiner's rejection, it would appear that the Examiner is not giving patentable weight

to the moisture displacing gas being nitrogen, since the Examiner asserts that Shimizu et al. shows the moisture displaying gas as nitrogen.

For the reasons stated above, reconsideration and withdrawal of this rejection are respectfully requested.

**Allowable Subject Matter**

Applicant thanks the Examiner for the indication that claims 1-4 and 6-12 are allowed. Further, Applicant thanks the Examiner for the indication that claim 15 would be allowable if rewritten in independent form. Claim 15 has been canceled and rewritten in independent form as new claim 17.

**CONCLUSION**

All of the stated grounds of rejection have been properly traversed, accommodated, or rendered moot. Applicant therefore respectfully requests that the Examiner reconsider all presently outstanding rejections and that they be withdrawn.

It is believed that a full and complete response has been made to the Office Action, and as such, the present application is in condition for allowance.

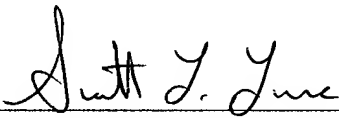
Should there be any outstanding matters that need to be resolved in the present application, the Examiner is respectfully requested to contact Mr. Scott L. Lowe (Reg. No. 41,458) at the telephone number of the undersigned below, to conduct an interview in an effort to expedite prosecution in connection with the present application.

Applicant(s) respectfully petitions under the provisions of 37 C.F.R. § 1.136(a) and 1.17 for a two-month extension of time in which to respond to the Examiner's Office Action. The Extension of Time Fee in the amount of \$420.00 is attached hereto.

If necessary, the Commissioner is hereby authorized in this, concurrent, and further replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

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